

WHAT IS CLAIMED IS:

1. A method of manufacturing a reticle for use in photolithography, comprising:

creating a first database of data representing coordinates, regions and process execution conditions for a plurality of pattern images to be transcribed onto different types of semiconductor products using a plurality of reticles in a photolithographic process, and classifying the data of said first database according to groups of similar types of the products;

creating a second database of data, representing process marks and boundaries of scribe lanes of the reticles, corresponding to each of the product groups;

for a selected product, inputting reference coordinates of the plurality of image patterns to be transcribed onto the selected product to extract from the second database the process marks and the scribe lane boundaries of reticles to be used for transcribing the image patterns onto the selected product;

determining at least one set of reference coordinates correlating each of the plurality of image patterns of the selected product with the corresponding scribe lane region boundaries extracted from the second database; and

designing and forming a reticle by batch-processing of the coordinates of the process mark.

2. The method of claim 1, wherein said determining of the reference coordinates comprises hypothetically selecting a center from the respective

coordinates of the scribe lane region based on relative positions of the plurality of pattern images.

3. The method of claim 1, wherein said determining of the reference coordinates further comprises selecting a reference point at one side provided from coordinates of the scribe lane region involving the regional position of the plurality of pattern images, the reference mark being for designating other reference coordinates.

4. The method of claim 1, wherein said designing and forming the reticle through the coordinates of the process mark includes batch applying each of coordinates formed through at least two or more determined reference coordinates to each of the pattern images.

5. The method of claim 1, wherein said designing and forming the reticle through the coordinates of the process mark includes one to one correspondence between the plurality of reference coordinates and coordinates provided in a region of the plurality pattern images to obtain the coordinates of the process mark, and a batch-processing of the coordinates to the respective pattern images.

6. A method of manufacturing reticles for use in manufacturing a semiconductor product using a photolithographic process, comprising:

creating a database including main chip circuit data associated with a pattern images to be formed at central regions of reticles, scribe lane region data representing

the form of a scribe lanes that are to surround the pattern images, respectively, and process marks that are to be formed in frames of the reticles located around the central regions of the reticles;

classifying the pattern image region data according to product groups, each of the product groups containing similar products that can be made using the photolithographic process;

labeling the process marks with reference coordinates;

for a specific one of the products to be manufactured, selecting process marks and the region of scribe lanes of the reticles to be used in manufacturing the products from the database on the basis of pattern image region data specific to the product;

automatically producing a layout of the selected process marks on the frames of the reticles, on the basis of combinations of the pattern image region data specific to the product and the selected scribe lanes; and

automatically drawing the process marks on the selected scribe lane regions of the reticles, respectively, using said layout.